OMNI Point-of-Use Gas Purifier Systems

FEATURES

- Integral purifier, heater, insulation and electronics assembly
- Compact design
- Easy-to-use
- Sub-ppb removal of impurities from Inert
- Gases, Hydrogen, Acid Gases, and Oxygen
- Certified temperature control unit and electronics designed for simple operation, reliability and safety
- Continual heated operation or room temperature operation with convenient in-situ operation

APPLICATIONS

- Analyzers (Zero/Calibration Gases)
- Analytical Carts
- Process Tools
- Research and Development
- Semiconductor Industry

The NuPure™ Omni series of Point-of-Use purifier systems incorporate the UltraPure® PF series® purifier-filter or UltraPure® XL series purifier, reducing gaseous impurities, (see chart below) to sub-ppb levels from Inert Gases, Hydrogen and Hydrides, Acid Gases and Oxygen. The PF series® includes particle filtration to 0.003 µm. The NuPure™ Purifier Systems are available in a standard range of 0 - 100 slpm.

The NuPure™ Omni Series is available in a wall mounted configuration offering a low cost fully integrated system including manual inlet, outlet and bypass valves, and optional gas particle filter.

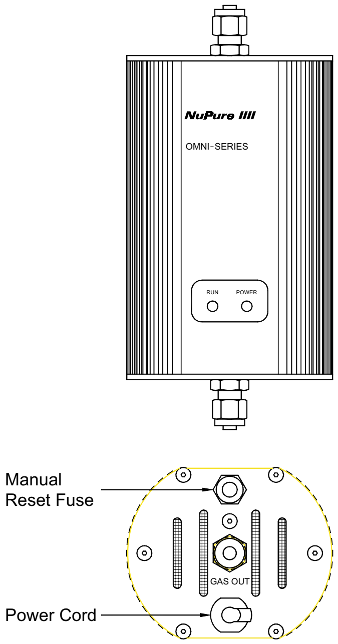
LISTING OF GASES PURIFIED / FILTERED

Inert Gases		**Hydrogen / Hydrides**		**Acid Gases**	**Oxygen**
Impurities Removed H_2O, O_2, CO, CO_2, H_2[1] (N_2, CH_4)[2]		Impurities Removed H_2O, O_2, CO_2, CO, (N_2)[3]		Impurities Removed H_2O	Impurities Removed H_2O, CO_2, (H_2, CO, CH_4)[4]
Ar	Ar/CH_4	H_2	AsH_3	HBr	O_2
He	CH_4	Ar/H_2	PH_3	HCl	Air
Ne	CF_4	N_2/H_2	NH_3	BCl_3	N_2O
Kr	CCl_4	SiH_4	B_2H_6	BF_3	
Xe	SF_6	Si_2H_6	H_2Se	Cl_2	
N_2	Freons	D.C.S.	GeH_4	HF	

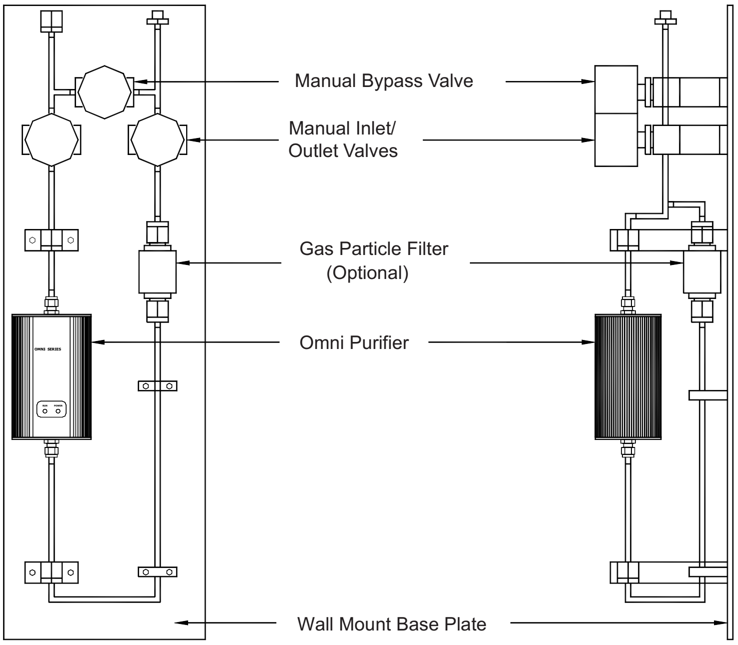
1 - Only with purchase of -H model. 2 - Additional impurities removed from He, Ne, Ar, Kr, Xe and N_2 only, using heated getter. 3 - Additional impurities removed from Hydrogen only, using heated getter. 4 - Only with purchase of optional heated catalyst.

NuPure™ Omni Series Point-of-Use Purifier

Technical Specification



Omni Series Purifier Module



Omni Series Purifier System

Model	Average Flows (slpm)[1] for 1 year lifetime (removal of impurities per chart page 1)	Max Flow (slpm) @ 150 psig (Heated)
Omni 40	0.3	1.5
Omni 100	1	5
Omni 200	2	10
Omni 600	6	30
Omni 1000	10	50
Omni 2000	20	100

Voltage	115/240 V AC
Housing	Extruded Aluminium 6063
Maximum Pressure	250 psig/9.9 kg/cm^{2}G (Japan)
Operating Temparature	375°C - 450°C
Leak Rate	$< 2 \times 10^{-10}$ atm cc/sec He
Materials (Purifier)	316L S.S. (< 10Ra)
Fittings	1/4" VCR[2]/ Compression
Gas Inlet	VLSI grade (99.9995%)

1 - Lifetime is inversely proportional to the total inlet impurity level and to the average flow. Lifetime for H_2O/O_2 removal only using getter purifiers is approx 4 years at the stated flows / inlet gas. Under nominal conditions.

2 - VCR compatible fitting standard. VCR® is a registered trademark of Cajon Corporation.

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